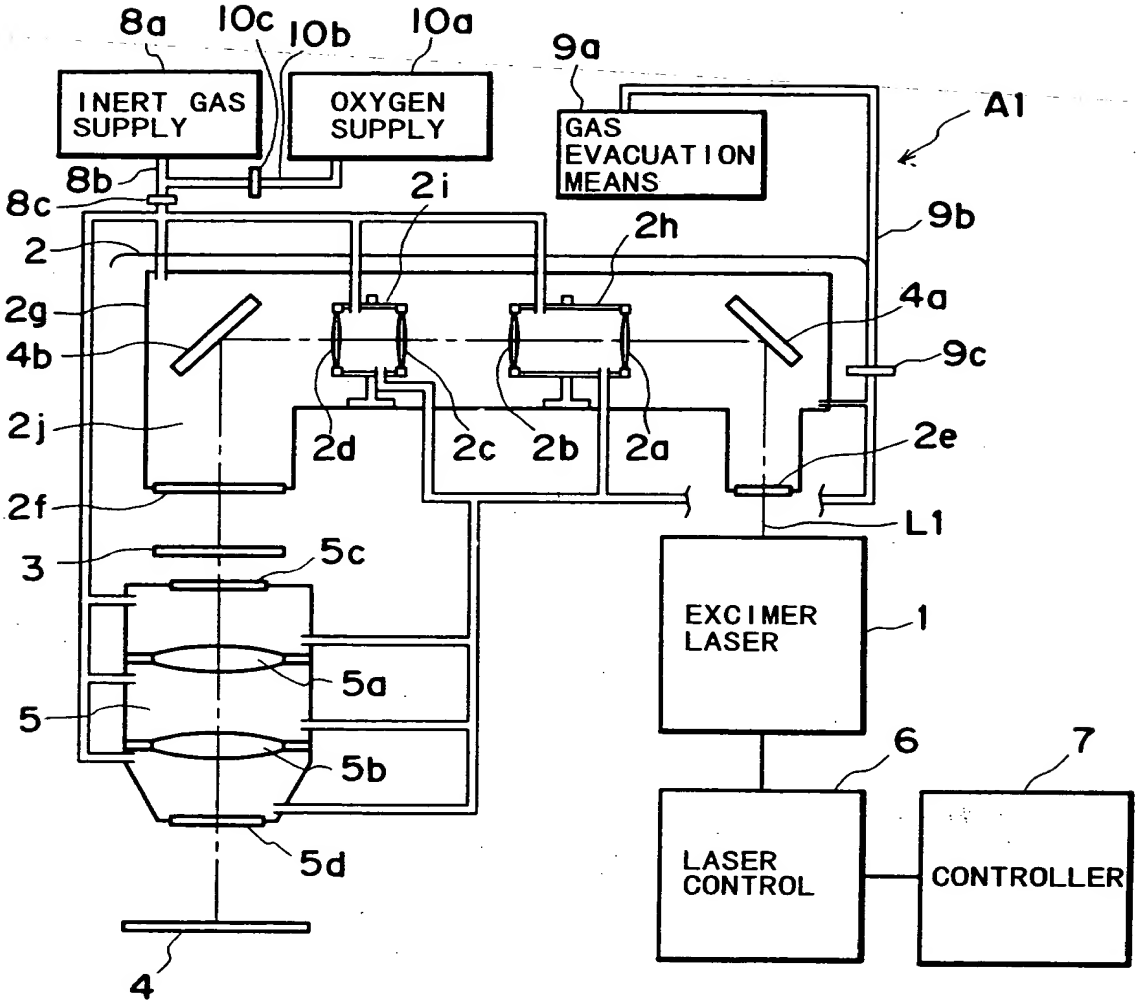
8a
10c
10b
10a
9a
INERT GAS SUPPLY
OXYGEN SUPPLY
GAS EVACUATION MEANS
A1
8b
8c
2i
2h
9b
2
2g
4b
4a
9c
2j
2d
2c
2b
2a
2e
2f
L1
3
5c
EXCIMER LASER
1
5a
5
5b
6
7
LASER CONTROL
CONTROLLER
5d
4

FIG. 1

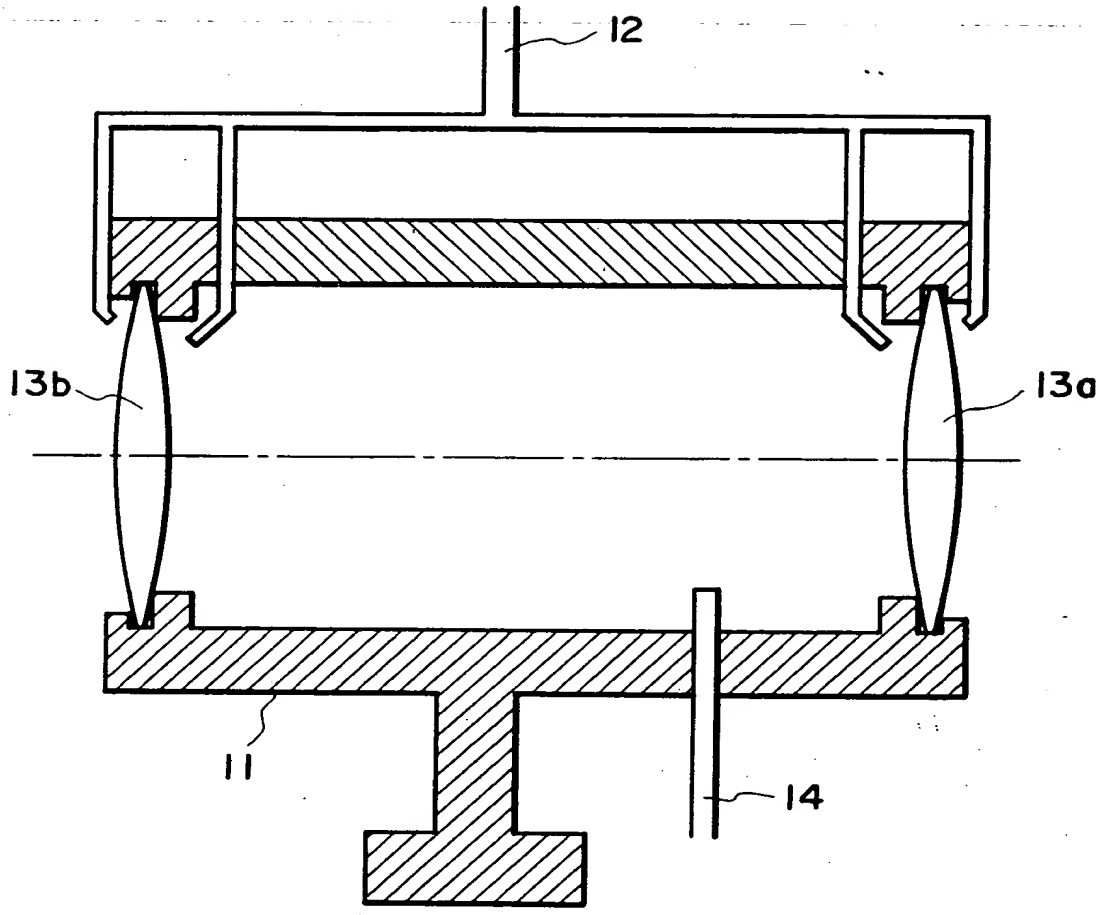

FIG. 2

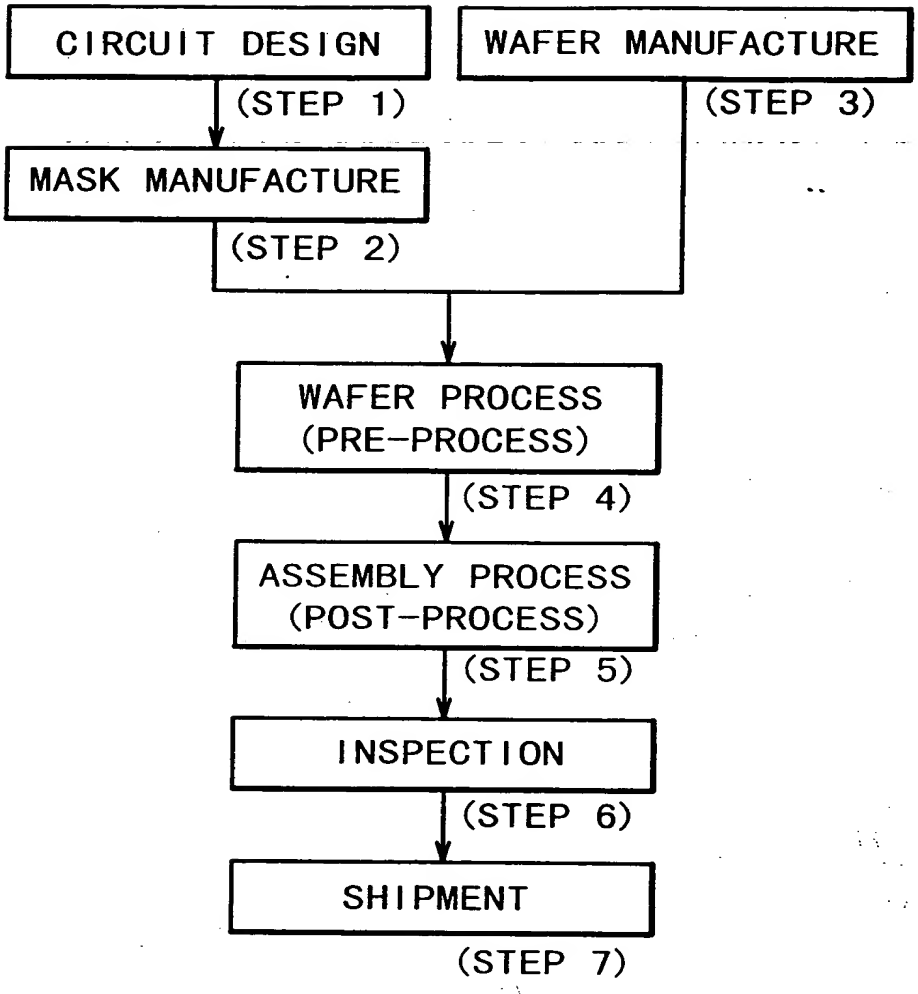
CIRCUIT DESIGN
(STEP 1)
WAFER MANUFACTURE
(STEP 3)
MASK MANUFACTURE
(STEP 2)
WAFER PROCESS
(PRE-PROCESS)
(STEP 4)
ASSEMBLY PROCESS
(POST-PROCESS)
(STEP 5)
INSPECTION
(STEP 6)
SHIPMENT
(STEP 7)

FIG. 3

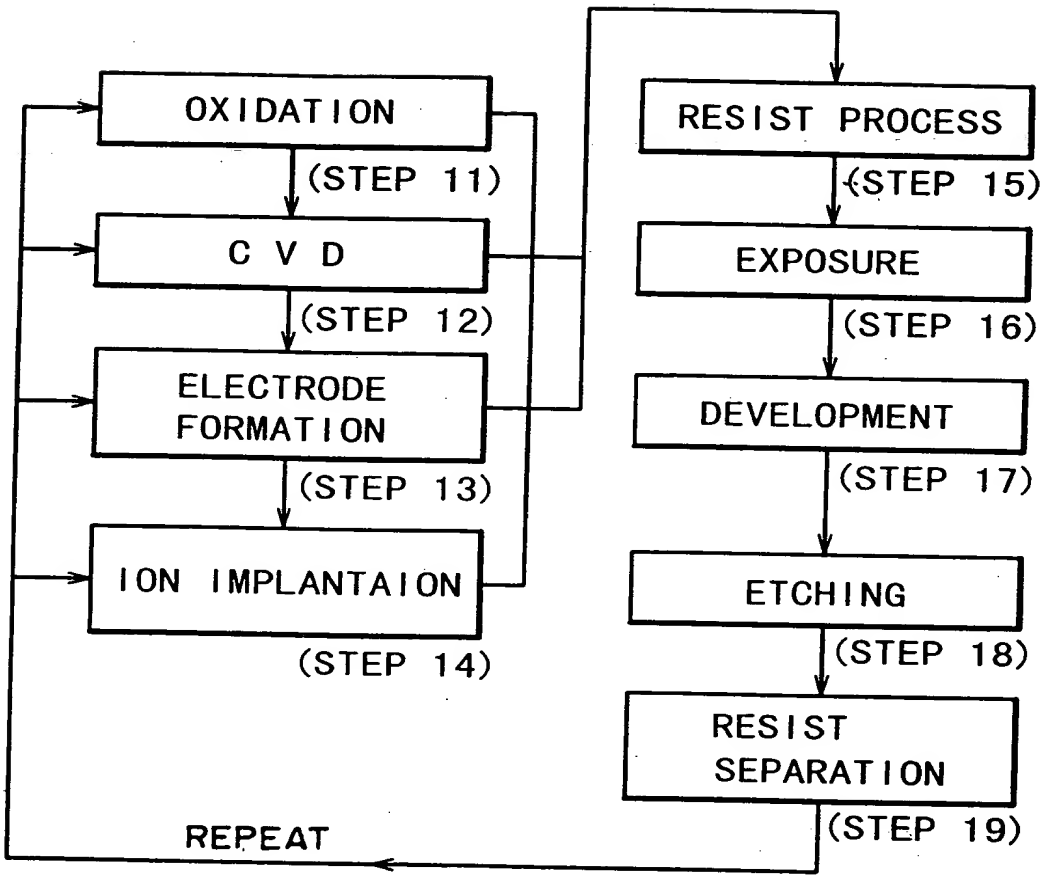
OXIDATION
(STEP 11)
C V D
(STEP 12)
ELECTRODE FORMATION
(STEP 13)
ION IMPLANTAION
(STEP 14)
RESIST PROCESS
(STEP 15)
EXPOSURE
(STEP 16)
DEVELOPMENT
(STEP 17)
ETCHING
(STEP 18)
RESIST SEPARATION
(STEP 19)
REPEAT

FIG. 4